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/ Ruth Montalvo Date: 01/07/05

Customer No. 026418

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Attorney's Docket No.: GK-ZEI-3262/500343.20282

U.S. Application No.:

International Application No.: PCT/EP03/07401

International Filing Date: JULY 09, 2003

09 JULY 2003

Priority Date Claimed: JULY 09, 2002

09 JULY 2002

Title of Invention:

ARRANGEMENT FOR THE PRODUCTION OF PHOTOMASKS

Applicant(s) for (DO/EO/US):

Thomas ENGEL, Wolfgang HARNISCH, Peter HOFFFROGGE and Axel ZIBOLD

Mail Stop PCT
Commissioner For Patents
P.O. Box 1450
Alexandria, VA 22313-450

INFORMATION DISCLOSURE STATEMENT

S I R:

Applicant herewith submits together with the simultaneously filed National Phase application of PCT/EP03/07401, a copy of the International Search Report (PCT/ISA/210) dated November 13, 2003 and German Examination Report (102 30 855.5) dated April 1, 2003, citing some of the following references:

	Document Number	Date	Name and/or Country	English Translation
AA	4,698,236	10/06/1987	Kellogg, et al.	n/a
AB	5,055,696	10/08/1991	Haraichi, et al.	n/a
AC	5,148,024	09/15/1992	Watanabe	n/a
AD	5,808,312	09/15/1998	Fukuda	n/a
AE	6,016,357	01/18/2000	Neary, et al.	n/a
AF	6,322,935	11/27/2001	Smith	n/a
AG	6,353,219	03/05/2002	Kley	n/a
AL	0 165 685	12/27/1985	European	n/a
AM	0 298 495	01/11/1989	European	n/a
AN	0 334 680	09/27/1989	European	n/a
AO	1 130 465	09/05/2001	European	n/a
AP	100 30 143	05/31/2001	Germany	Abstract only

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

AX Patent Abstracts of Japan, Publication No. 62-084518, published 18APR87
Hitachi Ltd.

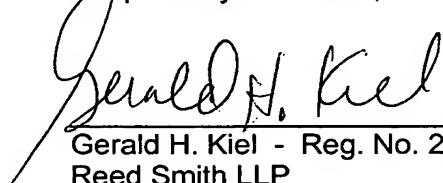
AY XP009020507, Use of Nanamachining for Subtractive Repair of EUV and Other
Challenging Mask Defects, David Brinkley, et al. Pages 900-911

Accompanying this Information Disclosure Statement and form PTO-1449 are copies of documents AA-AG first page only, AL-AP including 1 English Abstract, article and Abstract. Documents AB and AC are mentioned on page 1, paragraph [0003] 5 of the substitute specification.

The USPTO waived the requirement under 37 C.F.R. §1.98(a)(2)(i) for submitting copies of US patents and US patent application publications in all U.S. applications filed after June 30, 2003.

This submission is not an admission that the information disclosed in the documents is material to the patentability of the invention disclosed and/or claimed in the above-identified application.

Respectfully submitted,


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Enclosures:

Search Reports (PCT/ISA/210);
German Examination Report
PTO-1449;
7 US first pages;
5 Foreign documents w/1 English Abstract;
Article;
Patent Abstract of Japan

LIST OF PRIOR ART CITED BY APPLICANT
(Filed on January 7, 2004)

Docket No. **GK-ZEI-3262 / 500343.20282**Applicant(s): **Thomas ENGEL, Wolfgang HARNISCH, Peter HOFFROGGE and Axel ZIBOLD**

Application No. (Int'l Appln No. PCT/EP03/07401 09JUL03) Group:

Filed: Examiner:

U.S. PATENT DOCUMENTS

Exam. Init		Document Number	Date	Name	Class	Sub-Class	Filing Date Appropriate
	AA	4,698,236	10/06/1987	Kellogg, et al.			
	AB	5,055,696	10/08/1991	Haraichi, et al.			
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	AK						

FOREIGN PATENT DOCUMENTS

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	AL	0 165 685	12/27/1985	European				
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	AT							

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

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	AY	XP009020507, Use of Nanomachining for Subtractive Repair of EUV and Other Challenging Mask Defects, David Brinkley, et al. Pages 900-911
	AZ	

Examiner:

Date:

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.